

METHOD AND DEVICE FOR EXPOSURE CONTROL,  
METHOD AND DEVICE FOR EXPOSURE, AND  
METHOD OF MANUFACTURE OF DEVICE

ABSTRACT

5           A method for exposure control comprising the steps of  
measuring the change of the transmissivity or transmittance  
for the light incident to the projection optical system  
prior to the exposure operation effected by illuminating a  
pattern on a reticle to form an image of the pattern on a  
10   photosensitive wafer through the projection optical system,  
storing the measured change of the transmissivity,  
sequentially measuring the amount of the light incident to  
the projection optical system during the exposure operation,  
calculating the exposure light amount for the photosensitive  
15   wafer from the exposure light amount based on the stored  
change of the transmissivity, and integrating the exposure  
from the start of the exposure operation to terminate the  
exposure operation when the total exposure light amount has  
reached a predetermined value. The total exposure light  
20   amount for the wafer surface can be controlled even if the  
transmissivity of the projection optical system fluctuates.